

ABSTRACT

BISAMINOALKOXYLSILANE COMPOUNDS AND METHODS FOR USING SAME TO DEPOSIT SILICON-CONTAINING FILMS

5

Bisaminoalkoxysilanes of Formula I, and methods using same, are described herein:



10 where R¹ is selected from hydrogen, a C₁ to C₁₀ linear alkyl group, a C₃ to C₁₀ branched alkyl group, a C₃ to C₁₀ cyclic alkyl group, a C₂ to C₁₀ alkenyl group, a C₂ to C₁₀ alkynyl group, a C₄ to C₁₀ aromatic hydrocarbon group; R², R³, R⁴, and R⁵ are each independently selected from hydrogen, a C₄ to C₁₀ branched alkyl group, a C₃ to C₁₀ cyclic alkyl group, a C₂ to C₁₀ alkenyl group, a C₂ to C₁₀ alkynyl group, and a C₄ to C₁₀ aromatic hydrocarbon group; R⁶ is selected from a C₁ to C₁₀ linear alkyl group, a C₃ to C₁₀ branched alkyl group, a C₃ to C₁₀ cyclic alkyl group, a C₂ to C₁₀ alkenyl group, a C₂ to C₁₀ alkynyl group, and a C₄ to C₁₀ aromatic hydrocarbon group.

15